

IFW

PATENT
8074-1143

IN THE U.S. PATENT AND TRADEMARK OFFICE

In re application of

Koichi NANIWAE

Conf. unknown

Application No. 10/573,492

Group unknown

Filed March 24, 2006

Examiner unknown

METHOD OF CLEANING TREATMENT AND METHOD
FOR MANUFACTURING SEMICONDUCTOR DEVICESUPPLEMENTAL INFORMATION DISCLOSURE STATEMENTCommissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

June 27, 2006

Sir:

In compliance with Rules 1.97 and 1.98, and in fulfillment of the duty of disclosure under Rule 1.56, the accompanying document, a copy of which is attached to this statement, is made of record on the enclosed sheet.

A concise explanation of the relevance of this item is that this reference is discussed on pages 3 and 4 of the present specification.

Respectfully submitted,

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INFORMATION DISCLOSURE CITATION IN AN APPLICATION

Attorney Docket No.:

8074-1143

Application No.:

10/573,492

Applicant:

Koichi NANIWAE

(Use several sheets if necessary) JUN 27 2006

Filing Date:

March 24, 2006

Group Art Unit:

unknown

U.S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT DOCUMENTS

[illegible]

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

/E.J./	IEEE Journal Of Selected Topics In Quantum Electronics, Volume 3, Number 3, page 845 to page 853 (IEEE Journal of Selected Topics in Quantum Electronics, Vol. 3, NO. 3, p845 to p853)

EXAMINER:

/Eric Jones/

DATE CONSIDERED

8/20/2008

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

* Abstract provided for the Examiner's convenience